



Atty. Dkt. No. 039153-0381

9/5/03
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ramkumar SUBRAMANIAN, et al.
Title: TWO MASK PHOTORESIST EXPOSURE
PATTERN FOR DENSE AND ISOLATED
REGIONS
Appl. No.: 09/887,035
Filing Date: 06/25/2001
Examiner: K. Sagar
Art Unit: 1756

RECEIVED
SEP 03 2003
TC 1700

REQUEST FOR RECONSIDERATION

Mail Stop NON-FEE AMENDMENT
Commissioner for Patents
PO Box 1450
Alexandria, Virginia 22313-1450

Sir:

This communication is responsive to the Office Action dated June 5, 2003, concerning the above-referenced patent application.

The listing of claims begins on page 2 of this document.

Remarks/Arguments begin on page 9 of this document.

Please amend the application as follows:
